

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: Seok-Yoon YANG, et al. )  
Serial No.: 10/675,455 ) Group Art Unit: 1795  
Filed: September 30, 2003 ) Examiner:  
For: PHOTSENSITIVE RESIN COMPOSITION ) Walke, Amanda C.  
CONTROLLING SOLUBILITY AND PATTERN ) Confirmation No. 5598  
FORMATION METHOD OF DOUBLE-LAYER )  
STRUCTURE USING THE SAME )

OK TO ENTER: /ACW/

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

11/18/2008

**RESPONSE TO FINAL OFFICE ACTION  
UNDER 37 CFR § 1.116, WITH AMENDMENT**

Dear Sir:

In response to the Final Office action mailed on July 10, 2008, Applicants request reconsideration in view of the following remarks for entry in the above-identified application. This reply is being submitted with a Petition of one-month extension of time. Please charge an appropriate extension fee to Deposit Account No. 06-1130.

**Listing of the Claims** currently on file begins on page 2 of this paper; and  
**Remarks** begin on page 6 of this paper.

**Attachments:** Certified English translation for Korean Patent Application No. 10-2002-0060500 filed on October 4, 2002.